

ABSTRACT OF THE DISCLOSURE

The object of the present invention IS to provide an optical imprinting apparatus and method for producing a two-dimensional pattern, having line widths less than the wavelength of an exposure light. The evanescent (proximity) field effect is adopted to realize the apparatus and method. An optical imprinting apparatus comprises: a container in which light is enclosed therein; an exposure-mask having a proximity field exposure pattern firmly fixed to a section of said container for exposing said exposure pattern on a photo-sensitive material through an evanescent field by said light enclosed therein; and a light source for supplying said light in said container.